

## PATENT ABSTRACTS OF JAPAN

(11)Publication number : 09-090637

(43)Date of publication of application : 04.04.1997

(51)Int.Cl.

G03F 7/039

G03F 7/004

G03F 7/30

H01L 21/027

(21)Application number : 07-312722

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(22)Date of filing : 30.11.1995

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(30)Priority

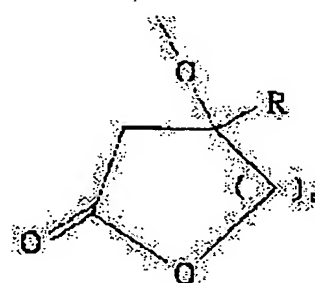
Priority number : 07178717 Priority date : 14.07.1995 Priority country : JP

## (54) RESIST COMPOSITION AND RESIST PATTERN FORMING METHOD

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a resist compsn. having a sensitivity capable of practical use and capable of forming a nonswellable fine resist pattern.

SOLUTION: An acid-sensitive polymer contained in this chemical amplification type resist compsn. in combination with an optical acid generating agent contains a lactone part represented by the formula [where R is optionally substd. 1-4C straight chain or branched chain alkyl and (n) is an integer of 1-4] as a protective group for each carboxyl group.



## LEGAL STATUS

[Date of request for examination]

24.03.2000

[Date of sending the examiner's decision of

rejection]

[Kind of final disposal of application other than  
the examiner's decision of rejection or  
application converted registration]

[Date of final disposal for application]

[Patent number] 3297272

[Date of registration] 12.04.2002

[Number of appeal against examiner's decision  
of rejection]

[Date of requesting appeal against examiner's  
decision of rejection]

[Date of extinction of right]

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